

Serial No. 10/795,979

Proposed Amendment dated February 15, 2006

Atty. Docket No. 249/437

Reply to Interview Summary mailed February 8, 2006

Proposed Amendment to Claim 21:

The proposed amendment to claim 21 would recite as follows:

21. (Currently Amended) A method of fabricating a pyroelectric emitter an electron beam lithography apparatus, comprising:
preparing a pyroelectric plate;
preparing a patterned mask of a semiconductor material,
including sequentially forming a semiconductor thin film
having a predetermined thickness and a resist on a dielectric
plate having the predetermined thickness, patterning the resist
in a predetermined pattern, patterning the semiconductor thin
film using the patterned resist as a mask, and removing the
patterned resist, the semiconductor material being sufficiently
thick in desired portions to prevent electrons emitted by the
pyroelectric plate during heating from being further
transmitted; [[and]]
disposing the patterned mask adjacent the surface of the
pyroelectric plate;
providing a heating source for heating the pyroelectric
emitter; and
providing a pair of magnets disposed beyond the
pyroelectric emitter and the substrate holder, respectively, to
control paths of electrons emitted by the pyroelectric emitter.